

## RESIST REMOVER RR4

### Description

- Resist Remover RR4 is a stripping solution designed to remove photoresist from the surface of a substrate.

### Properties

◆ Principal solvent	dimethyl sulfoxide
◆ Melting temperature (°C)	18
◆ Appearance	clear liquid
◆ Specific gravity at 25°C (g/cm <sup>3</sup> )	1.00-1.05
◆ Guaranteed shelf life at 25°C storage (years)	3

### Processing

1. Pour the solution into a resist stripping tank.
2. Heat the solution to 110°C under an exhaust hood.
3. Place the resist coated substrate in the solution for 5 minutes.
4. Rinse the substrate with deionized water until the water resistivity reaches the prescribed limit.